

November 18, 2003

Commissioner for Patents P.O.Box 1450 Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572 28 Davis Avenue Poughkeepsie, N.Y. 12603

Subject:

Serial No. 10/647,715 08/25/03

Horng-Huei Tseng

A MIM CAPACITOR HAVING A HIGH-DIELECTRIC-CONSTANT INTERELECTRODE INSULATOR AND A METHOD OF FABRICATION

Grp. Art Unit:

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56. Copies of each document is included herewith.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on November 7/, 2003.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

- U.S. Patent 6,084,765 to Lee, "Integrated Circuit Capacitors Having Recessed Oxidation Barrier Spacers," discusses integrated circuit capacitors utilizing improved spacers to protect diffusion barrier layers from parasitic oxidation and capacitor electrodes from being overetched.
- U.S. Patent 5,877,062 to Horii, "Methods of Forming Integrated Circuit Capacitors Having Protected Diffusion Barrier Metal Layers Therein," discloses methods of forming integrated circuit capacitors including the steps of forming an electrically insulating layer having a contact hole therein, on a face of a semiconductor substrate and then forming a polysilicon contact plug in the contact hole.
- U.S. Patent 6,232,133 to Kim et al., "Method for Fabricating a Capacitor of Semiconductor Memory Device," provides a method for fabricating a capacitor of semiconductor memory device, which can prevent Ti from diffusing into the ferroelectric layer of capacitor from the Ti adhesive layer.
- U.S. Patent 6,277,702 to Chun et al., "Capacitor of a Semiconductor Device and a Method of Fabricating the Same," discloses a storage element of a stacked capacitor having a high dielectric film for a semiconductor device and a method of fabricating the same.

TSMC-01-1629

U.S. Patent 5,994,197 to Liao, "Method for Manufacturing Dynamic Random Access Memory Capable of Increasing the Storage Capacity of the Capacitor," discloses a method for manufacturing the capacitor of a dynamic random access memory cell.

Sincerely,

Stephen B. Ackerman, Reg. No. 37761

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citation if not in conformance and not considered. Include copy of this form with next communication to the applicant